Program at a Glance

As of June 2026

June 23rd

Room A Medium Hall
Tutorial Session 13:00-14:40
Coffee Break
Tutorial Session 14:55-16:25
Coffee Break
Tutorial Session 16:40-18:20
Closing Remark
Welcome Reception 18:30-20:00

June 24th

Room A Medium Hall	Room B Small Hall	Room C Room 407
Opening 9:30-9:45		
Award 9:45-10:00		
E0. Plenary Talk 10:00-11:30		
E2 EUV Lithography 13:00-14:40	E12 Fundamentals and Applications of Biomimetics Materials and Processes 13:00-14:40	E11 Organic and Hybrid Materials for Photovoltaic and Optoelectronic Devices 13:30-15:25
Coffee Break	Coffee Break	Coffee Break
E2 EUV Lithography 14:55-15:55	E12 Fundamentals and Applications of Biomimetics Materials and Processes 15:00-16:00	E11 Organic and Hybrid Materials for Photovoltaic and Optoelectronic Devices 15:40-17:00
Coffee Break		
E4 Computational / Analytical Approach for Lithography Processes 16:10-18:10		
Coffee Break		
Panel Symposium 18:30-20:00		

June 25th

Room A Medium Hall	Room B Small Hall	Room C Room 407	Room D Room 408
E2 EUV Lithography 9:30-11:30	E7 Strategies, Materials, and Processes for Advanced Packaging, MEMS, and Flexible Devices 9:20-11:25	E11 Organic and Hybrid Materials for Photovoltaic and Optoelectronic Devices 9:30-11:00	E13, J1 Surface Treatment and Functionalization of Polymer Surfaces 9:20-10:20
			Coffee Break
			E13, J1 Surface Treatment and Functionalization of Polymer Surfaces 10:30-11:30
		Coffee Break	
General Assembly 11:40-12:45		E11 Organic and Hybrid Materials for Photovoltaic and Optoelectronic Devices 11:15-12:30	
E2 EUV Lithography 13:00-15:00	E8 Polyimides and High Thermally Stable Resins 13:00-14:20	E10 Photopolymers in 3-D Printing/ Additive Manufacturing 13:30-14:50	E13, J1 Surface Treatment and Functionalization of Polymer Surfaces 13:30-14:20
	Coffee Break		Coffee Break
Coffee Break	E7 Strategies, Materials, and Processes for Advanced Packaging, MEMS, and Flexible Devices 14:30-16:00	Coffee Break	E13, J1 Surface Treatment and Functionalization of Polymer Surfaces 14:30-15:30
E1 Next Generation Lithography and EB Lithography		E10 Photopolymers in 3-D Printing/ Additive Manufacturing 15:00-16:30	
E3 DUV Lithography 15:15-17:05	Coffee Break		
	E7 Strategies, Materials, and Processes for Advanced Packaging, MEMS, and Flexible Devices 16:10-17:20	E5 Directed Self Assembly (DSA) 16:30-17:10	
Banquet 17:30-20:00			

June 26th

Room A Medium Hall	Room B Small Hall	Room C Room 407
E5 Directed Self Assembly (DSA) 9:30-11:00	E9 Nanobiotechnology 9:30-12:00	E6 Nanoimprint 9:30-10:30
E2 EUV Lithography 13:00-14:40		E14 Chemistry for Advanced Photopolymer Science 13:30-14:30
Coffee Break		Coffee Break
E2 EUV Lithography 14:55-16:15		E14 Chemistry for Advanced Photopolymer Science 14:50-15:50
Closing Remark 16:20-16:30		